Amendments to the Claims:

Please amend the claims as indicated.

1. (Previously Presented) A patterning system comprising:

a bifurcated heat transfer mechanism having a surface; and

a source to direct thermal energy toward said bifurcated heat transfer mechanism, with said bifurcated heat transfer mechanism collecting said thermal energy and conducting said thermal energy to said surface.

2. (Original) The system as recited in claim 1 wherein said bifurcated heat transfer mechanism further includes developing a localized heat source proximate to said surface.

3. (Previously Presented) The system as recited in claim 1 wherein said system further includes a mold positioned between said bifurcated heat transfer mechanism and said source to allow said energy to propagate therethrough.

4. (Previously Presented) The system as recited in claim 1 wherein said system further includes an imprinting layer positioned between said bifurcated heat transfer mechanism and said source to allow said thermal energy to propagate therethrough.

5. (Original) The system as recited in claim 1 wherein said bifurcated heat transfer mechanism comprises a carbon black composition.

6. (Original) The system as recited in claim 1 wherein said bifurcated heat transfer mechanism is permanently disposed within said system.

7. (Original) The system as recited in claim 1 wherein said bifurcated heat transfer mechanism is removably disposed within said system.

8. (Currently Amended) A patterning system comprising:

a source of radiation to direct radiation toward a target;

a wavelength discriminator to selectively allow first and second subsets of said radiation to reach said target, with said first subset including thermal energy;

a mold positioned to allow said first and second subsets to propagate there through; and

a thermal absorption layer, having a surface, disposed to collect said first subset and develop a localized heat source therein having heat energy associated therewith, with said heat source ~~conducing~~ conducting said heat energy to said surface while maintaining a constant phase state.

9. (Original) The system as recited in claim 8 wherein said system further includes an imprinting layer positioned between said mold and said thermal absorption layer to allow said first subset to propagate there through.

10. (Original) The system as recited in claim 8 wherein said thermal absorption layer comprises a carbon black composition.

11. (Original) The system as recited in claim 8 wherein said thermal absorption layer is permanently disposed within said system.

12. (Original) The system as recited in claim 8 wherein said thermal absorption layer is removably disposed within said system.

13. (Original) The system as recited in claim 8 wherein said constant phase state comprises a solid phase state.

14. (Previously Presented) A patterning system comprising:

a source of radiation to direct radiation, having multiple wavelengths including thermal radiation, along a path, with said path extending between said source and a target;

a wavelength discriminator to selectively allow a subset of said radiation to travel toward said target; and

a bifurcated heat transfer mechanism having a surface disposed between said wavelength discriminator and said target to collect said thermal radiation and develop heat energy therein, and to conductively transfer said heat energy to said surface.

15. (Original) The system as recited in claim 14 wherein said system further includes a mold positioned between said bifurcated heat transfer mechanism and said source of radiation to allow said radiation to propagate there through.

16. (Original) The system as recited in claim 14 wherein said system further includes an imprinting layer positioned between said bifurcated heat transfer mechanism and said source of radiation to allow said thermal radiation to propagate there through.

17. (Original) The system as recited in claim 14 wherein said bifurcated heat transfer mechanism comprises a carbon black composition.

18. (Original) The system as recited in claim 14 wherein said bifurcated heat transfer mechanism is permanently disposed within said system.

19. (Original) The system as recited in claim 14 wherein said bifurcated heat transfer mechanism is removably disposed within said system.

20. (New) A patterning system comprising:

a bifurcated heat transfer mechanism having a surface;

a source of radiation to direct said radiation toward said bifurcated heat transfer mechanism, with said bifurcated heat transfer mechanism being responsive to said radiation such that said bifurcated heat transfer mechanism collects said radiation to generate thermal energy and transferring said thermal energy to said surface; and

an imprinting layer positioned between said bifurcated heat transfer mechanism and said source of radiation to allow said radiation to propagate therethrough.

21. (New) A patterning system comprising:

a source of radiation to direct infrared radiation toward a target;

a wafer;

a mold positioned between said source of radiation and said wafer to allow said infrared radiation to propagate therethrough;

an imprinting layer positioned on said wafer to allow said infrared radiation to propagate therethrough; and

a thermal absorption layer, positioned between said imprinting layer and said wafer, disposed to collect said infrared radiation and develop a localized heat source therein having heat energy associated therewith, with said heat source conducting said heat energy to said imprinting layer through said wafer while maintaining a constant phase state.

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